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Page 2 of 10**IN THE CLAIMS**

Please cancel claims 13-16 without prejudice or disclaimer.

Please substitute the following amended claims for the corresponding original claims. A marked copy of the claim amendments is attached hereto.

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12. (amended) A substrate processing chamber comprising:

- (a) a support having a receiving surface capable of supporting a substrate;
- (b) a gas distributor capable of providing process gas in the chamber and a gas energizer that is capable of coupling energy to the process gas;
- (c) a radiation transmitting portion that allows radiation to be transmitted therethrough to monitor processing of the substrate;
- (d) a mask overlying the radiation transmitting portion, the mask having an aperture comprising an aspect ratio that is selected to reduce deposition of process residue on the radiation transmitting portion, the aspect ratio being from about 1:1 to about 12:1; and
- (e) an exhaust capable of exhausting process gas from the chamber.

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Please add the following new claims:

129. (new) A substrate processing chamber comprising:

- (a) a support having a receiving surface capable of supporting a substrate;
- (b) a gas distributor capable of providing process gas in the chamber and a gas energizer that is capable of coupling energy to the process gas;
- (c) a radiation transmitting portion that allows radiation to be transmitted therethrough to monitor processing of the substrate;
- (d) a mask overlying the radiation transmitting portion, the mask having an aperture comprising an aspect ratio that is selected to reduce deposition of process residue on the radiation transmitting portion, the aspect ratio being from about 0.25:1 to about 3:1; and
- (e) an exhaust capable of exhausting process gas from the chamber.

129. (new)

130. (new) A substrate processing chamber according to claim 1 wherein the mask comprises an array of hexagonal apertures.